

¹ ABSTRACT OF THE DISCLOSURE

an X-ray mask support comprises a support
frame and a support film, wherein both of the support
frame and the support film have a thermal expansion
5 coefficient of not more than $1 \times 10^{-5} \text{K}^{-1}$ or wherein
the thermal expansion coefficient of the support film
does not exceed that of the support frame or wherein
both the support frame and the support film have a
thermal expansion coefficient of not more than
10 $1 \times 10^{-5} \text{K}^{-1}$ and the support film has a surface
roughness at least on the mask surface, of not more
than 10 nm r.m.s. Basically a process for preparing
the X-ray support film comprises the steps of forming
a film on a substrate and sintering the film.

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